

Structure, Microstructure and Physical properties of ZnO based Materials Invarious Forms : Bulk, Thin film and Nano



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ABSTRACT

ZnO is a unique material that offers about a dozen different application possibilities. In spite of the fact that the ZnO lattice is amenable to metal ion doping (3d and 4f), the physics of doping in ZnO is not completely understood. This paper presents a review of previous research works on ZnO and also highlights results of our research activities on ZnO. The review pertains to the work on Al and Mg doping for conductivity and bandgap tuning in ZnO followed by a report on transition metal (TM) ion doped ZnO. This review also highlights the work on the transport and optical studies of TM ion doped ZnO, nanostructured growth (ZnO polycrystalline and thin films) by different methods and the formation of unique nano- and microstructures obtained by pulsed laser deposition and chemical methods. This is followed by results on ZnO encapsulated Fe₃O₄ nanoparticles that show promising trends suitable for various applications. We have also reviewed the non-linear characteristic studies of ZnO based heterostructures followed by an analysis on the work carried out on ZnO based phosphors, which include mainly the nanocrystalline ZnO encapsulated SiO₂, a new class of phosphor that is suitable for white light emission.

Introduction

Like most other wide band gap semiconductors, ZnO has already been studied in the 1970s before being neglected in the field of microelectronics. The study and growth of this material have been revisited in the past few years because of its attractive fundamental properties and numerous application possibilities. The technical progress made in synthesis (bulk and nano) and epitaxial growth of thin films and the results indicate the possibility of realizing both n-type and p-type conduction in ZnO [1]. Making p-type ZnO is still a challenge and remains an intriguing issue [2,3]. The domains of interest for compounds based on ZnO and associated heterostructures are optoelectronics and spintronics. On comparing the key properties (table 1) of ZnO with some of the competing compound semiconductors, it is obvious that there is enormous potential for ZnO in optoelectronic applications. Indeed ZnO has a unique combination of

high band gap energy (~ 3.4 eV) and excitonic stability. The high excitonic energy (~ 60 meV) makes it a potential candidate for light emission applications [4–7]. This also gives strong resistance to high temperature electronic degradation during operation (e.g. laser diodes).

Al and Mg doped ZnO products such as flat panel displays, solar cells, optoelectronic and electronic components and thermally insulating architectural glass have one thing in common. They have a combination of transparency and electrical conductivity. The only way to obtain a good transparent conductor is to create electron degeneracy in a wide band gap (> 3 eV) oxide by introducing non-stoichiometry and/or by appropriate doping (n- or p-type). It is well known that non-stoichiometric and doped films of oxides based on, e.g., tin, indium, cadmium, gallium, copper, zinc and their blends exhibit high transmittance and electrical conductivity. The electronic properties of ZnO are of much importance in other applications such as transient voltage suppressors and ultraviolet protective additives in the manufacture of plastics [36]. Generally, the trivalent elements, such as Al, Ga and B [37], are used as donor dopants in ZnO thin films. ZnO doped with Ga or Al exhibits carrier concentrations of 6×10^{20} cm⁻³ and 7.5×10^{20} cm⁻³, respectively [38–41]. Al doped ZnO samples have been studied extensively till now. Yuan and Cordaro demonstrated the changes in the electronic properties of Al doped ZnO powders with the help of optical reflectance characteristics [42]. Hsiao et al [43] synthesized Al doped ZnO (AZO) nanostructured powders via a spray pyrolysis technique.

Piezoelectric property of ZnO

For creating and designing micro-electromechanical systems (MEMS), new functional materials should be integrated on various substrates. Piezoelectric thin films, such as lead zirconate-titanate (PZT), boron doped diamond and oxidized zinc (ZnO), are the key materials for designing MEMS systems. Although the piezoelectric property is of major importance for the properties of MEMS, not much attention was given to measuring the piezoelectric coefficient of the deposited thin film. Since the piezoelectric thin film is mostly deposited by sputtering and sol/gels [98,99], the piezoelectric coefficient is affected by the deposition conditions to improve the properties. Very little research work has focused on the material composition and deposition conditions. Among the above-mentioned materials ZnO exhibits both semiconducting and piezoelectric properties that can form the basis for electromechanically coupled sensors and transducers.

CONCLUSION

In this report the growth of crystalline ZnO, in bulk, thin films and nano forms by various chemical and physical techniques, has been presented. A review on the tuning of band gap and resistivity with Mg and Al doping, respectively, was presented. The key issues for the device application of ZnO in optoelectronics include the growth of high quality layers of n-type conductivity, the possibility of dissolving transition elements in the lattice and the growth of ZnO nanostructures and heterostructures, all of which have been featured in this review. It is shown that TM-ion doping in ZnO brings about a decrease in electrical resistivity for Fe, Co, Ni, V and Ti doping and in the case of Cr, Mn doping,

resistivity is found to increase. The significant aspects of the PLD technique, such as various growth pressures, substrates and doping, have been specifically addressed. Interesting changes in microstructures have been observed in TM ion doped ZnO, along with changes in the physical properties of the parent compound. The possibility of realizing ZnO based magnetic nanoparticles and phosphor has also been discussed.

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